

(12) PATENT APPLICATION PUBLICATION

(21) Application No.202011011186 A

(19) INDIA

(22) Date of filing of Application :16/03/2020

(43) Publication Date : 17/09/2021

(54) Title of the invention : NANOLITHOGRAPHY METHOD

(51) International classification	:G03F0007000000, G03F0007200000, H01L0033460000, B33Y0010000000, B33Y0030000000	(71)Name of Applicant : 1)CGC Technical Campus Jhanjeri Address of Applicant :State Highway 12A Jhanjeri, Sahibzada Ajit Singh Nagar, Punjab 140307, India. Punjab India
(31) Priority Document No	:NA	(72)Name of Inventor : 1)Dr. Kiran Uttreja
(32) Priority Date	:NA	
(33) Name of priority country	:NA	
(86) International Application No	:NA	
Filing Date	:NA	
(87) International Publication No	: NA	
(61) Patent of Addition to Application Number	:NA	
Filing Date	:NA	
(62) Divisional to Application Number	:NA	
Filing Date	:NA	

(57) Abstract :

The present invention relates to a nanolithography method, comprising the steps of base material deposition over a semiconductor base, an oxide formation according to the user defined patter, etching the pattern by deploying a diluted acid over the pattern to create vacant space along with the pattern, layering a second material over the vacant space and removing the base material by dipping the surface inside an etchant of the base material which results in leftover of print of the desired material over the semiconductor.

No. of Pages : 11 No. of Claims : 9